

Sustainable cleaning chemistry for semiconductor production

# **GreenClean - Intelligent Fluid - IFTiN**

#### **Project information** 1

## **Conventional chemicals**





Pyrazol/NMP basedt

**DMSO/TMAH** based

VS.

- Petroleum-based & solvent
- Reprotoxicity or strong skin penetration
- High application temperatures & energy requirements
- Aggressive towards equipment & material
- Very high disposal costs



- Water-based
- Protects material & equipment
- Low application temperature & energy saving
- Patented microemulsion-based phase fluid technology

### **Technology & fields of application** 2

### **Project description** 3





Cleaning is one of the most important and

Lift-off process tests on coupons have already

shown high effectiveness





essential steps in microelectronics in backend-of-line wiring production or the structuring of other metallizations.

- It has to be repeated many times.
- With up to 13 copper levels on top of each other, it is one of the most important cleaning steps in semiconductor devices.



Replacement of critical cleaning chemicals in a representative industrial use case, benchmarking and life cycle assessment using a reference process.

GEFÖRDERT VOM

.Resist

Low-k

Liner/Cu

Etch/Ash

Residual

removal

SCREEN

HM (TiN)

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